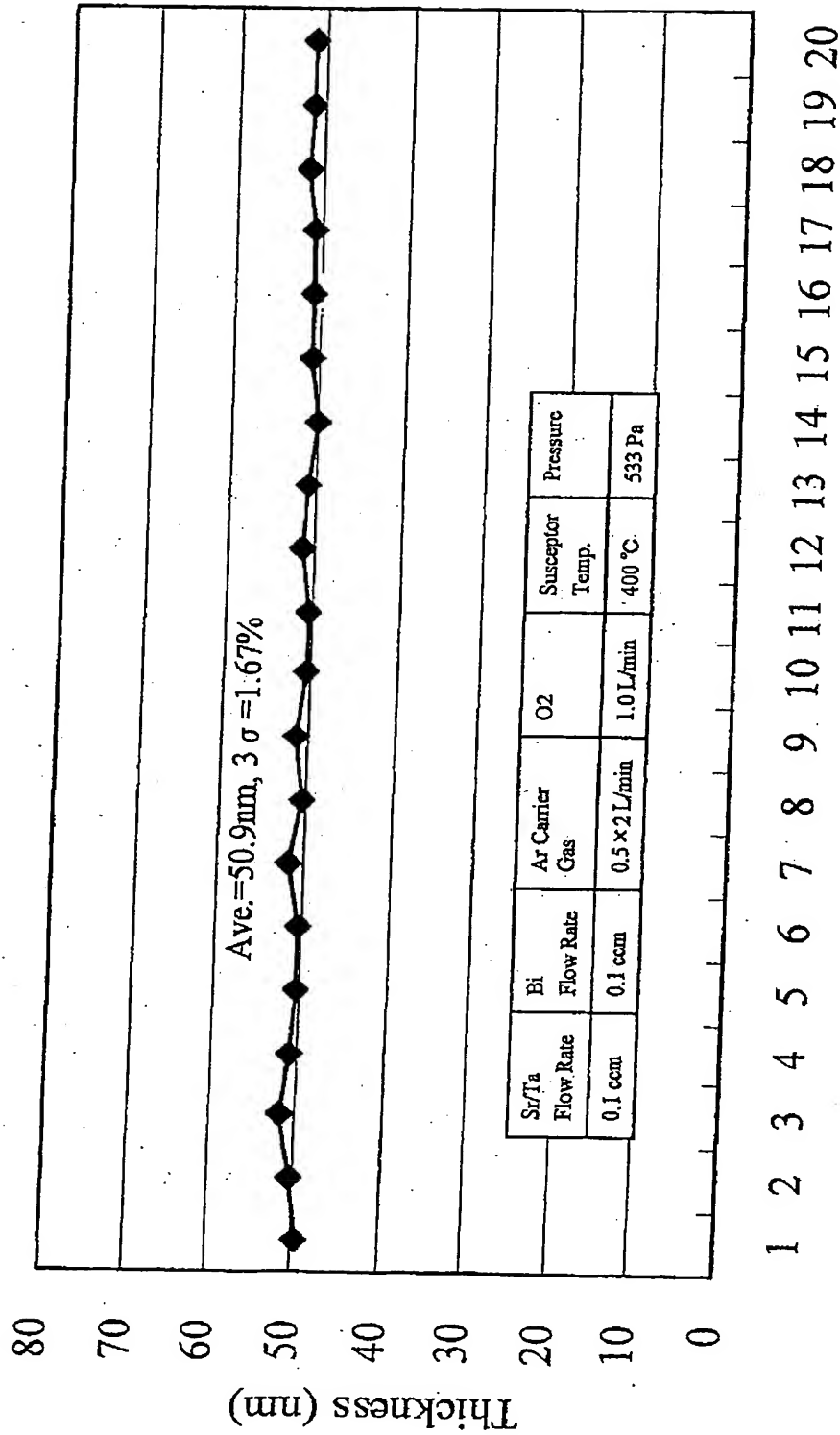


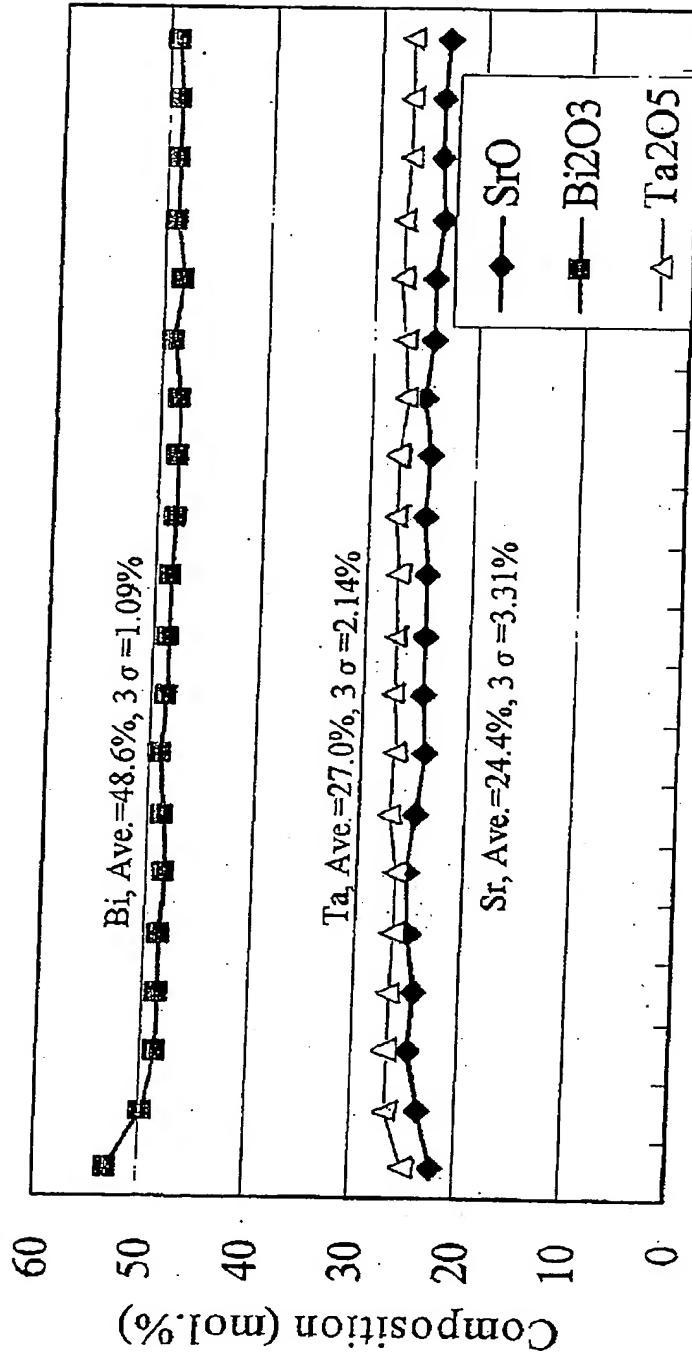
# Continuous Running Test Result (SBT Thickness, Si Wafer)



No.

SBT Precursors:  $\text{Sr}[\text{Ta}(\text{OEt})_5(\text{OC}_2\text{H}_4\text{OMe})]_2$  / ECH (0.1mol/L),  $\text{Bi}(\text{MMP})_3$  / ECH (0.2mol/L)

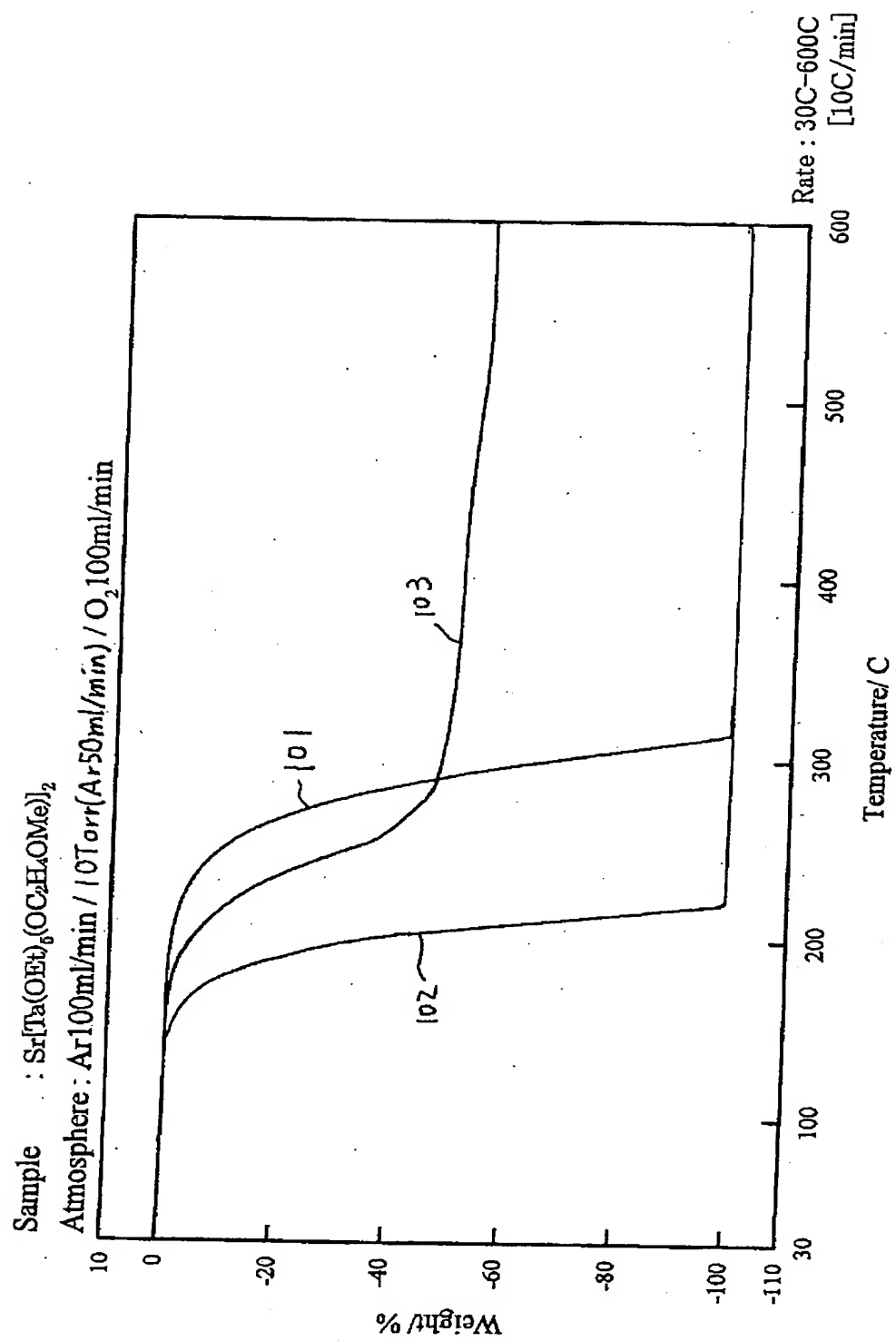
# Continuous Running Test Result (SBT Composition, Si Wafer)

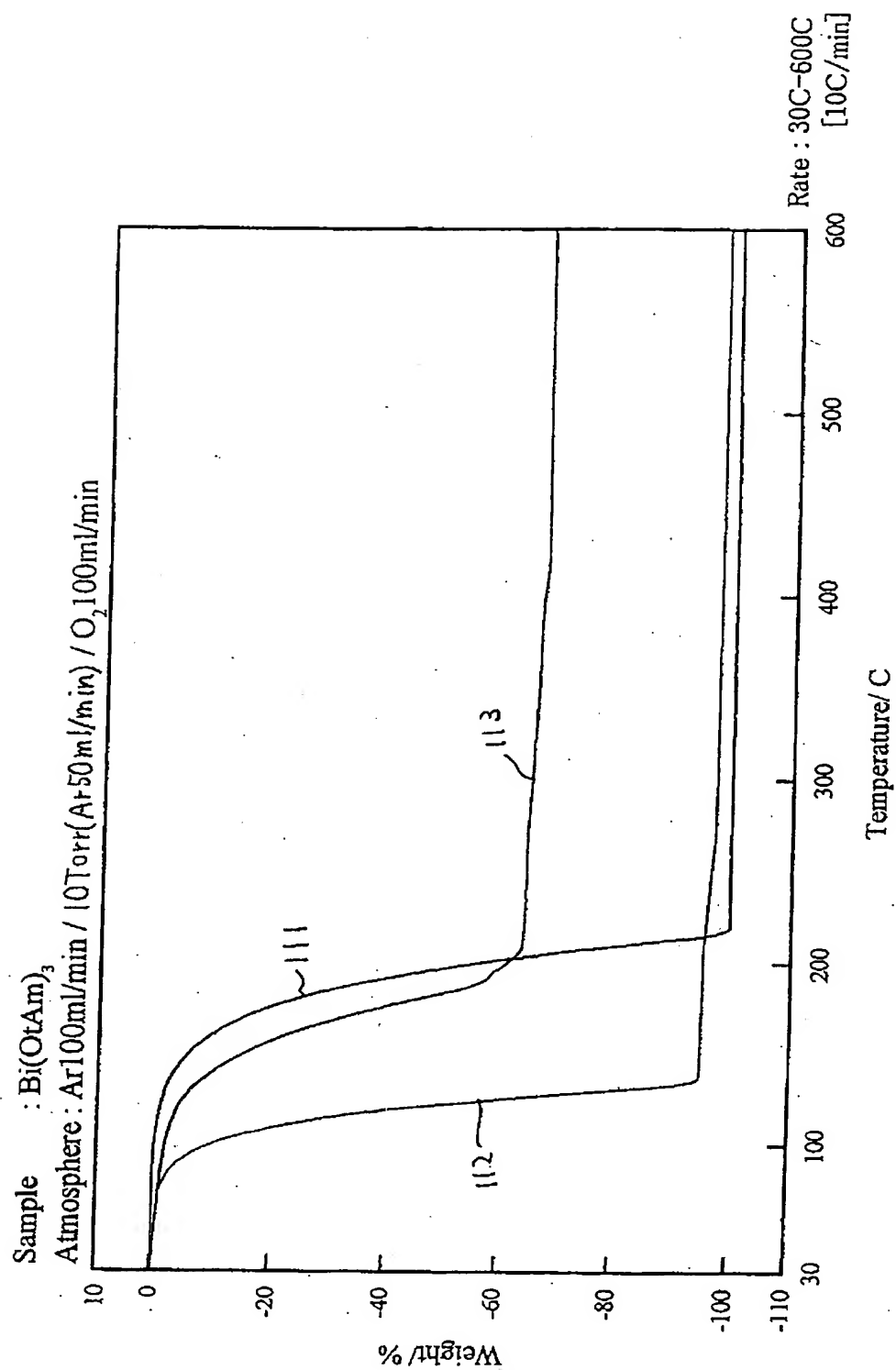


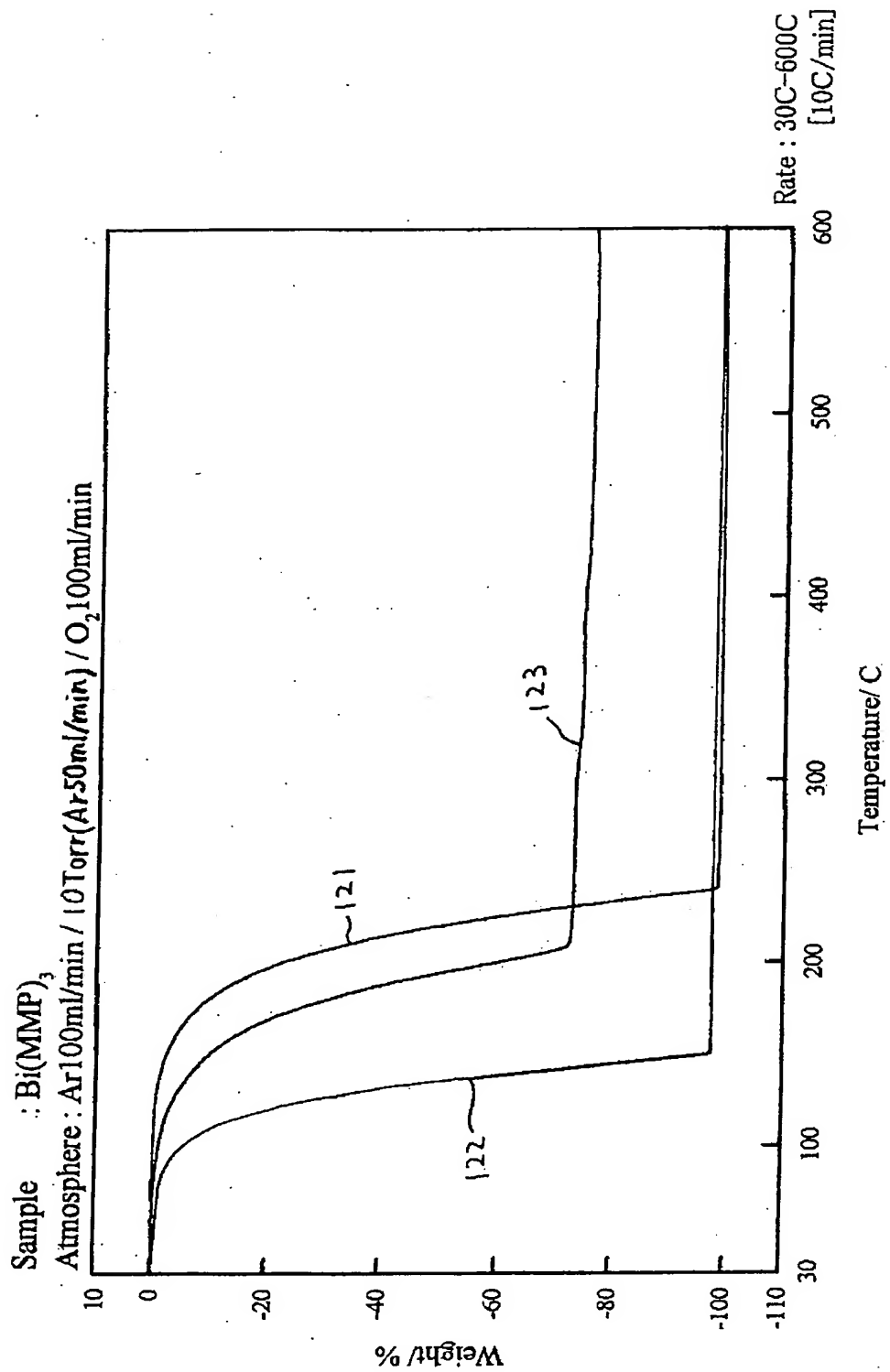
No.

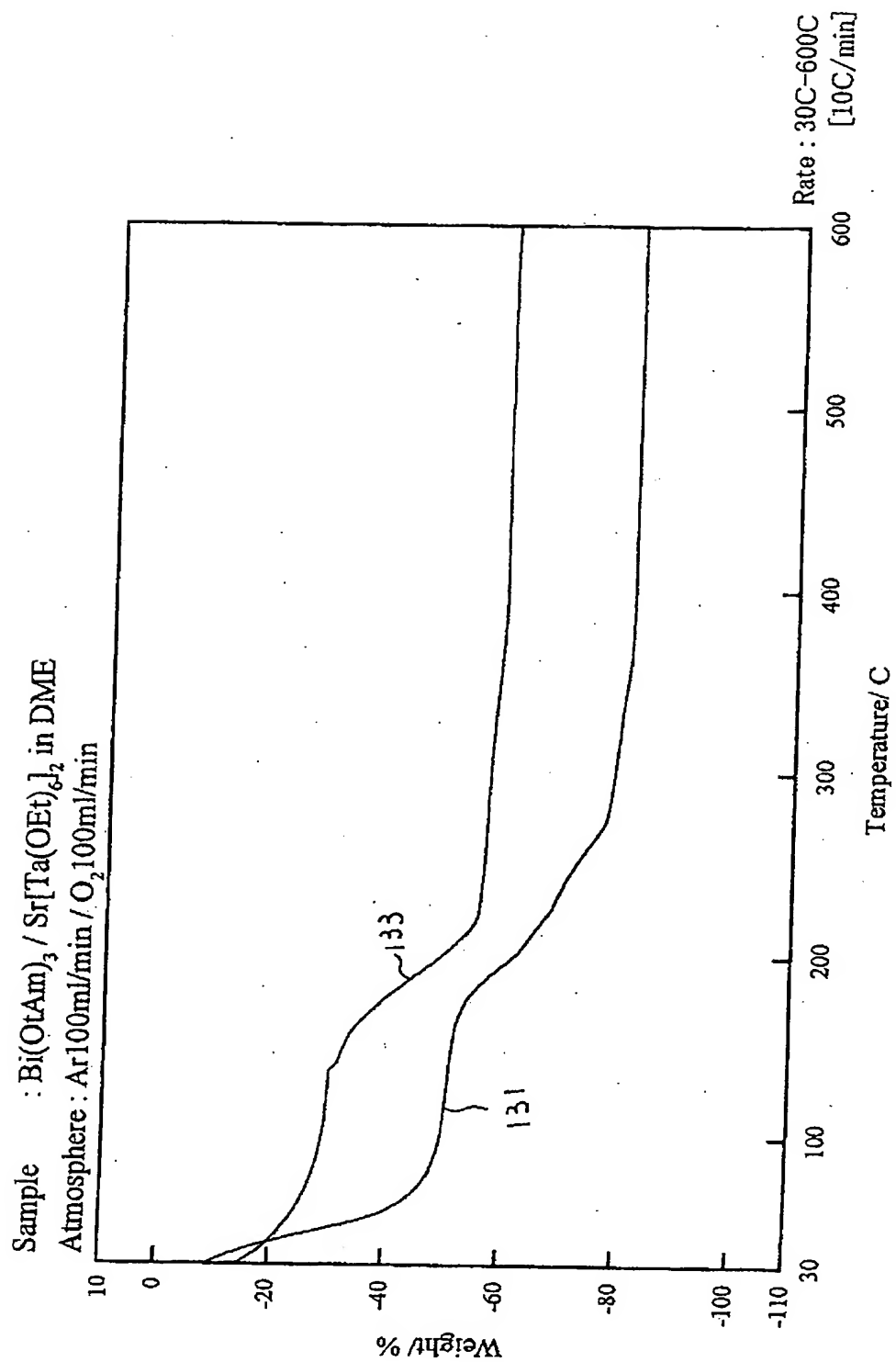
Sr/Ta Flow Rate	Bi Flow Rate	Ar Carrier Gas	O <sub>2</sub>	Susceptor Temp.	Pressure
0.1 ccm	0.1 ccm	1.0 L/min	1.0 L/min	400 °C	533 Pa

SBT Precursors: Sr[Ta(OEt)<sub>5</sub>(OC<sub>2</sub>H<sub>5</sub>OMe)]<sub>2</sub>/ECH (0.1mol/L), Bi(MMP)<sub>3</sub>/ECH (0.2mol/L)









*Mixing Stability of  $\text{Bi}(\text{OtAm})_3$  &  $\text{Sr}[\text{Ta}(\text{OEt})_6]_2$  (NMR)*

